High-Frequency Modeling and Optimization of E/O Response and Reflection Characteristics of 40 Gb/s EML Module for Optical Transmitters

Chengzhi Xu, Y.Z. Xu, Yanli Zhao, Kunzhong Lu, Weihua Liu, Shibing Fan, Hui Zou, and Wen Liu

A complete high-frequency small-signal circuit model of a 40 Gb/s butterfly electroabsorption modulator integrated laser module is presented for the first time to analyze and optimize its electro-optic (E/O) response and reflection characteristics. An agreement between measured and simulated results demonstrates the accuracy and validity of the procedures. By optimizing the bonding wire length and the impedance of the coplanar waveguide transmission lines, the E/O response increases approximately 5% to 15% from 20 GHz to 33 GHz, while the signal injection efficiency increases from approximately 15% to 25% over 18 GHz to 35 GHz.

Keywords: Electroabsorption modulator integrated laser (EML), E/O response, reflection characteristics, circuit model, butterfly packaging, optical transmitter.

I. Introduction

The single channel data rate of the optical communication system has increased from 10 Gb/s to 40 Gb/s and can reach up to 100 Gb/s. Achieving these faster rates requires optoelectronic components with higher performance in terms of stability, modulation bandwidth, extinction ratio, and package size. The monolithic integration of an electroabsorption modulator (EAM) and a distributed feedback laser is a promising solution due to the component’s compact size, high optical output power, high modulation bandwidth, low cost, low driving voltage operation, and excellent extinction ratio [1]-[4]. For a 40 Gb/s application, the bandwidth margin of the electroabsorption modulator integrated laser (EML) chip is small; therefore, careful radio frequency design is needed to achieve the performance for the packaged module. For high-speed application, the optoelectronic components inside the package may interfere with each other if the structure of the package is not chosen properly. Two types of mainstream packaging are popular for high-speed optoelectronic devices: the butterfly package [5] and the transistor outline (TO) package [6], [7]. The high-frequency electric signal of the TO-type package is fed in through the RF pin, and its microwave performance can hardly meet the requirements of 40 Gb/s applications. Nevertheless, the size of the TO-type package is too small to dissipate the heat generated by a high-power thermoelectric cooler. To meet the high-frequency electro-optic (E/O) response requirement, the radio frequency electric signal input ports of a 14-pin butterfly package housing have been replaced by high-
frequency coaxial connectors, such as V or GPPO connectors, which have better microwave performance. This packaging technique is also widely deployed in high-speed transponders, transmitters, small form modules, and some novel optoelectronics components.

To understand the characteristics and behaviors under various configurations inside a module, it is very important to construct a high-frequency model of the modules. Regarding earlier models, the presenting researchers derived significant analysis of the frequency characteristics of the laser module. Lee and others proposed a complete small-signal model of a butterfly-type 2.5 Gb/s DFB laser module [8]. Delpiano and others described a high-frequency model of a DFB laser module with which they analyzed and optimized the main factors contributing to the bandwidth limitation of the module [9]. A small-signal equivalent TO-type package laser module was presented by Zhu and others, where the effects of each element on the high-frequency response were analyzed [10]. Great improvement and low cost packaging can be achieved with these proposed models. However, there is so far no report or analysis on a model of an EML butterfly package with a high-frequency coaxial connector.

In this paper, we propose a complete high-frequency small-signal circuit model of a 40 Gb/s EML butterfly package with a V-type coaxial connector and analyze its frequency characteristics. The 40 Gb/s EML module includes a V connector butterfly package, a high-frequency submount, bonding wires, and an EML chip. A test platform for an EML chip on a submount and an EML module is built. E/O response (S21) and reflection characteristics (S11) are measured and compared with the simulated data to validate the circuit model. This high-frequency model is employed to optimize the bonding wire length and the impedance of the coplanar waveguide (CPW) transmission lines, and the E/O response and the reflection performance are greatly improved.

II. Model of EML Chip and Measurement Setup

1. Small-Signal Model of EML Chip

Figure 1 shows a typical structure of an InGaAlAsP multiple-quantum-well (MQW) EML chip. An InGaAlAsP MQW EML chip is grown by a combination of selective area growth and several other epitaxial growth steps by means of metal organic chemical vapor deposition. The EML consists of a DFB laser section that operates in the CW mode, and an EAM section that modulates the output light. The two sections are separated by an isolation section. The small-signal equivalent circuit model of the EML chip is derived based on this structure, as shown in Fig. 2.

Capacitance C2 in the model represents the parasitic capacitance generated by the solder joint, while C1 represents the junction capacitance, which consists of the capacitance of the MQW active region and the capacitance of the indium phosphate layers. R1 and R2 represent the device resistance and the resistance generated by photocurrent, respectively. The EAM section operation is reverse biased and connected to the DFB laser through an isolation trench, which has a large resistance (represented by R3, as in Fig. 2). The resistance of the isolation trench is usually larger than 3 kΩ; therefore, the DFB laser will not be interfered with by the high-frequency characteristic of the EAM. The DFB laser can then be represented by a PIN diode.

2. Network Theoretical Description

The measurement theoretical configuration for the EML module can be divided into three cascaded networks: 1) the network of the test fixture, the package parasitic element, and the intrinsic EAM in the EML chip (represented by network P); 2) the intrinsic network of the laser in the EML chip (represented by network L); and 3) the network of the receiver (represented by network R). The scattering parameters of the EML and the receiver can be written as [11]

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Fig. 1. Typical structure of InGaAlAsP MQW EML.

Fig. 2. Small-signal equivalent circuit model of EML chip.
The intrinsic laser can be negligible compared with the serial resistance $R_3$, and $S_{11}^-\text{L}$ can be regarded as $-1[12]$. Meanwhile, at high reverse bias currents, the receiver can be replaced by an open circuit [13], and $S_{22}^P$ can be regarded as 1. The T-matrix of the whole measured EML module can be written as

$$T = T^P T^{LR} = \frac{1}{S_{21}^P S_{21}^R} \begin{bmatrix} S_{12}^P S_{21}^R - S_{11}^P S_{22}^P, S_{11}^P \quad 1, S_{11}^L \end{bmatrix} \begin{bmatrix} 0, 1, 0, 1 \end{bmatrix} \begin{bmatrix} S_{21}^P, S_{22}^P, S_{21}^R, S_{22}^R \end{bmatrix}$$ (2)

By transforming the above T-matrix to S-parameters, we have

$$S_{11}^P = \frac{S_{21}^P S_{21}^R - S_{12}^P S_{22}^P}{1 + S_{22}^P}, \quad S_{21}^P = \frac{S_{21}^P S_{22}^R}{1 + S_{22}^P}. \quad (3)$$

From (3), we can see that the reflection coefficient depends only on the cascade of the test fixture, the package parasitic element, and the intrinsic EAM in the EML chip. Therefore, we can extract the values of these fixtures, the package parasitic element, and the intrinsic parameters of the EAM from the measured S11 by a traditional curve fitting method [14].

3. Measurement Setup

The measurement setup is shown in Fig. 3. The high-frequency microwave signal with a frequency of up to 40 GHz is fed through a V-type connector to a butterfly-packaged EML module or through a high-frequency CPW probe (GGB 58801) to the submount with the EML chip. The microwave signal is generated by a network analyzer (Agilent 8722ET). A reverse voltage is loaded to the EAM by a DC bias tee. The output light is amplified by an EDFA and then converted to an electrical RF signal by a photodetector ($u^t$ 40G), which is connected to a network analyzer. In theory, we can test the total frequency response of the test fixture, the receiver, and the device under test (DUT). A de-embedding method is employed in this test. The responses of the test fixture and the receiver are pre-embedded in the test system so that we can directly obtain the small-signal response of the DUT. The S21 result is simply the E/O response of the DUT in the test. The image of the test EML chip on the submount is shown in Fig. 4.

III. Small-Signal Model of 40 Gb/s Butterfly EML Module

1. EML Chip on Submount

Figure 5 shows the small-signal circuit model of the EML chip on the submount. Inductor $L_1$ and resistor $R_4$ represent the inductance and resistance of the bonding wire, which connects the EAM electrode of the chip to the signal line of the CPW on the submount. $C_3$ represents the capacitance of the submount. There is a 50 $\Omega$ thin film resistor represented by $R_5$, shunted with the EML chip on the submount to ensure the total impedance of around 50 $\Omega$. The inductance and resistance of the bonding wire between the EA electrode of the chip and the 50 $\Omega$ thin film resistor are represented by $L_2$ and $R_6$, respectively. With the laser diode biased at 60 mA and the EAM reverse biased at $-2.1$ V, the S11 and S21 of the EML chip on the submount are measured, as shown in Fig. 6. The commercial high-frequency computer-aided design package (Advanced Design System) is used to extract the parameters by a traditional curve fitting method. The extracted values of the small-signal model for the EML chip on the submount are shown in Table 1. The measured curves agree well with the...
Table 1. Extracted values of small-signal model for EML chip on submount.

<table>
<thead>
<tr>
<th>Components</th>
<th>Extracted values</th>
<th>Components</th>
<th>Extracted values</th>
</tr>
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<tbody>
<tr>
<td>L1 (nH)</td>
<td>0.256</td>
<td>R1 (Ω)</td>
<td>13.68</td>
</tr>
<tr>
<td>L2 (nH)</td>
<td>0.161</td>
<td>R2 (Ω)</td>
<td>132.23</td>
</tr>
<tr>
<td>C1 (pF)</td>
<td>0.021</td>
<td>R3 (Ω)</td>
<td>3200.00</td>
</tr>
<tr>
<td>C2 (pF)</td>
<td>0.054</td>
<td>R4 (Ω)</td>
<td>1.74</td>
</tr>
<tr>
<td>C3 (pF)</td>
<td>0.102</td>
<td>R5 (Ω)</td>
<td>50</td>
</tr>
<tr>
<td>R6 (Ω)</td>
<td>0.667</td>
<td></td>
<td></td>
</tr>
</tbody>
</table>

fitting curves.

2. Small-Signal Circuit Model of Complete Butterfly 40 Gb/s EML Modules

The RF part of the EML module consists of an EML chip, a submount with a CPW, and a submount with a microstrip line that connects high-frequency signals from a V-type high-frequency coaxial connector with a CPW on the submount. The optical output beam from the EML chip is coupled with a single-mode fiber that has an optics system containing two aspherical lenses. A CPW is used to optimize the impedance characteristic of the device and improve the frequency response of the module. For a complete small-signal circuit model of the butterfly 40 Gb/s EML module, we combine the small-signal model of the EML chip on the submount with parasitic components, which include a high-frequency V coaxial connector, a microstrip line, a CPW, and bonding wires. Figure 7 shows the complete small-signal circuit model of the EML module. Based on the network theory as described in [11], we have the element values listed in Table 2. Figure 8 shows the measured and simulated data, which demonstrates...
Table 2. Extracted parameters of the complete small-signal model for EML module.

<table>
<thead>
<tr>
<th>Parameter</th>
<th>Description</th>
<th>Value</th>
</tr>
</thead>
<tbody>
<tr>
<td>L3 (nH)</td>
<td>Inductance from bonding wire that connects microstrip to CPW</td>
<td>0.05</td>
</tr>
<tr>
<td>L4, L5 (nH)</td>
<td>Inductance from high-frequency V-type connector</td>
<td>0.002</td>
</tr>
<tr>
<td>R7 (Ω)</td>
<td>Resistance from bonding wire that connects microstrip to CPW</td>
<td>0.30</td>
</tr>
<tr>
<td>C4 (pF)</td>
<td>Capacitance from microstrip</td>
<td>0.002</td>
</tr>
<tr>
<td>C5 (pF)</td>
<td>Capacitance from high-frequency V-type connector</td>
<td>0.020</td>
</tr>
</tbody>
</table>

Fig. 7. Schematic drawing and small-signal model of complete butterfly-type 40 Gb/s EML modules.

Fig. 8. Simulated and measured S11 and S21 of butterfly 40 Gbps EML module with 60 mA current, and –2.1 V reverse bias. Agreement at the measuring frequency range up to 28 GHz.

IV. Effects of Bonding Wires and Optimizing of Module

1. Effects of Bonding Wire on Module Based on Model

As we know, the bonding wire will introduce parasitic inductance and this cannot be neglected, especially in the package with a frequency over 10 GHz. The distance between the EML chip and the 50 Ω thin film resistor is relatively short, and so is the distance between the CPW and the microstrip. Therefore these bonding wires can be taken as fixed values. L1, which connects the EA electrode of chip to the CPW on the submount, becomes the only key parasitic inductance. In our package, the inductance of a typical single diameter of 1 mil wire is about 0.7 nH/mm. The lengths of L2 and L3 are 0.23 mm and 0.07 mm, respectively. Figure 9 shows the simulated S11 of the module in terms of bonding wire length L1. The length of L1 should not exceed 0.4 mm so as to maintain a return loss below –10 dB for a frequency range up to 28 GHz.

Fig. 9. Simulated S11 with variable wire bonding lengths of L1.

2. Optimization of the Module

Good E/O response and low input return loss depend not only on the EML chip itself but also on other package components. For a typical EML module, a characteristic impedance of the CPW transmission lines on an aluminium nitride submount is selected as 50 Ω. From this high-frequency small-signal circuit model, we found that there was a large impedance mismatch between the EML chip and such
conventional CPW transmission lines especially at a high frequency. The RF performance of the module can be improved by optimizing the impedance match of the EML chip and the CPW. However, the impedance of the EML chip is not easy to modify, since changing the impedance of the EML chip will add other trade-offs. For example, if we further reduce the capacitance of the EML chip to improve the RF response by reducing the EA modulator length, other characteristics such as extinction ratio will degrade. Therefore, to reduce the impedance mismatch, it is proposed here to optimize the CPW transmission lines on the submount by using the proposed model. It is found that an optimized 42 Ω characteristic impedance of the CPW transmission lines has the best match with the EML chips. Figure 10 shows the measured frequency response of the EML module with the optimized CPW. We can see that the input return loss is below –10 dB up to 35.2 GHz, and the 3 dB frequency response bandwidth is 33.1 GHz. In the latter case, the signal injection efficiency increases from approximately 15% to 25% over 18 GHz to 35 GHz, while the modulation bandwidth increases approximately 5% to 15% from 20 GHz to 33 GHz. With this model we can improve the RF performance of the EML module by optimizing the design and the matching of different components one by one in the package.

V. Conclusion

In this paper, we proposed a small-signal equivalent circuit model of a 40 Gb/s butterfly EML module. Our method employed a step-by-step measurement and fitting procedure to build the model. In each step, an agreement between measurement and simulation results was achieved, and the stability of the extracted values of each parasitic element demonstrated the accuracy of the model. The proposed model was used to optimize the length of the bonding wire and the CPW submount, while the E/O and reflection characteristics of the EML module were greatly improved.

References


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